

ABSTRACT OF THE DISCLOSURE

A plasma processing apparatus includes a chamber
in which a plate to be processed is contained,
an introductory port via which a hydrogen-atom-
5 containing gas is guided into the chamber, a lower
electrode on which the plate is laid in the chamber,
an upper electrode disposed opposite to the lower
electrode and causing electric discharge in the chamber
to produce a plasma, a power supply which supplies
10 voltage between the lower and upper electrodes, and
a metal oxide structural body disposed in a part in the
chamber, the metal oxide structural body being reduced
when the hydrogen-atom-containing gas is introduced.